

INTERNATIONAL STANDARD



**Semiconductor devices – Flexible and stretchable semiconductor devices –
Part 9: Performance testing methods of one transistor and one resistor (1T1R)
resistive memory cells**

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CONTENTS

FOREWORD	3
1 Scope	5
2 Normative references	5
3 Terms and definitions	5
4 Device under testing (DUT)	7
5 Test method	8
5.1 General.....	8
5.2 Test equipment and tools	8
5.2.1 General	8
5.2.2 Read	9
5.2.3 Forming	10
5.2.4 SET programming.....	11
5.2.5 RESET programming	12
5.2.6 Endurance	14
5.2.7 Retention.....	16
5.3 Test report	17
Bibliography.....	18
Figure 1 – 1T1R resistive memory cell	8
Figure 2 – Block diagram of the measurement setup of 1T1R resistive memory cells	9
Figure 3 – Read operation of 1T1R resistive memory cell	9
Figure 4 – Cumulative probability distribution of HRS and LRS of 1T1R resistive memory cells	10
Figure 5 – Forming operation of 1T1R resistive memory cell	11
Figure 6 – Simulation test flow chart of the forming process.....	11
Figure 7 – SET operation of 1T1R resistive memory cell	12
Figure 8 – Simulation test flow chart of the SET operation of 1T1R resistive memory cell	12
Figure 9 – RESET operation of 1T1R resistive memory cell	13
Figure 10 – Simulation test flow chart of the RESET operation of 1T1R resistive memory cell	13
Figure 11 – Cumulative resistance distribution of 1T1R resistive memory	14
Figure 12 – Simulation test flow chart of the endurance test of 1T1R resistive memory cell	15
Figure 13 – Exemplary endurance data of a 1T1R resistive memory cell.....	15
Figure 14 – Simulation test flow chart of retention property of 1T1R resistive memory cells	16
Figure 15 – Exemplary retention characteristics of 1T1R resistive memory cells	16

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**SEMICONDUCTOR DEVICES – FLEXIBLE AND
STRETCHABLE SEMICONDUCTOR DEVICES –**
**Part 9: Performance testing methods of one transistor
and one resistor (1T1R) resistive memory cells**

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The text of this International Standard is based on the following documents:

Draft	Report on voting
47/2781/FDIS	47/2791/RVD

Full information on the voting for its approval can be found in the report on voting indicated in the above table.

The language used for the development of this International Standard is English.

This document was drafted in accordance with ISO/IEC Directives, Part 2, and developed in accordance with ISO/IEC Directives, Part 1 and ISO/IEC Directives, IEC Supplement, available at www.iec.ch/members_experts/refdocs. The main document types developed by IEC are described in greater detail at www.iec.ch/standardsdev/publications.

A list of all parts in the IEC 62951 series, published under the general title *Semiconductor devices – Flexible and stretchable semiconductor devices*, can be found on the IEC website.

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- withdrawn,
- replaced by a revised edition, or
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SEMICONDUCTOR DEVICES – FLEXIBLE AND STRETCHABLE SEMICONDUCTOR DEVICES –

Part 9: Performance testing methods of one transistor and one resistor (1T1R) resistive memory cells

1 Scope

This part of IEC 62951 specifies the test methods for evaluating the performance of unipolar-type one transistor one resistor (1T1R) resistive memory cells. The performance test methods in this document include read, forming, SET, RESET, endurance and retention. This document is applicable to flexible devices as well as rigid resistive memory devices without any limitations prone to device technology and size.

2 Normative references

There are no normative references in this document.

3 Terms and definitions

For the purpose of this document, the following terms and definitions apply.

ISO and IEC maintain terminological databases for use in standardization at the following addresses:

- IEC Electropedia: available at <http://www.electropedia.org/>
- ISO Online browsing platform: available at <http://www.iso.org/obp>

3.1

programming transistor

semiconductor device used to amplify, limit or switch electronic signals and electrical power

3.2

source voltage

V_S

bias applied to the source terminal of the programming transistor

3.3

gate voltage

V_G

bias applied to the gate terminal of the programming transistor

3.4

drain voltage

V_D

bias applied to the drain terminal of the programming transistor

3.5

resistive memory

two terminal device, based on reversible formation and rupture of filament within active layer, defining low and high resistance states, respectively

3.6 forming voltage

V_{Form}

high voltage applied across the active layer to induce defects within the active layer to form a filament or conduction path initially

3.7 resistance of low resistance state

R_{LRS}

resistance of memory device in SET state

3.8 resistance of high resistance state

R_{HRS}

resistance of memory device in RESET state

3.9 trip point resistance

R_{TRP}

intermediate reference resistance between R_{HRS} and R_{LRS}

$$R_{\text{HRS}} > R_{\text{TRP}} > R_{\text{LRS}}$$

3.10 step voltage

V_{Step}

ramp of voltage intervals applied to resistive memory

3.11 read voltage

V_{Read}

specific voltage for measuring the resistance of resistive memory, R_{R}

3.12 read current

I_{Read}

specific current value at V_{Read} for measuring the resistance of resistive memory, R_{R}

3.13 resistance of resistive memory

R_{R}

resistance value at V_{Read} , defined by the following formula

$$R_{\text{R}} = \frac{V_{\text{Read}}}{I_{\text{Read}}}$$

3.14 SET voltage

V_{SET}

voltage required to switch resistive memory to R_{LRS} after forming process

**3.15
RESET voltage** V_{RESET} voltage required to switch resistive memory to R_{HRS} **3.16
SET time** t_{SET} time required to switch resistive memory to R_{LRS} **3.17
RESET time** t_{RESET} time required to switch resistive memory to R_{HRS} **3.18
programming transistor on voltage** V_{ON}

voltage required to turn on programming transistor

**3.19
delay time** t_{Delay} required time between V_{R} and V_{G} for stable operation**3.20
pulse width** t_{R}

elapsed time between the rising and falling edges of a single pulse -a5f0-4910e65d9390/iec-62951-9-2022

4 Device under testing (DUT)

Figure 1 a) shows the equivalent circuit of 1T1R resistive memory cell. The top electrode of the resistive memory, the source, gate and drain of the transistor are defined as terminal V_{R} , V_{S} , V_{G} and V_{D} , respectively. Figure 1 b) shows the schematic diagram of 1T1R resistive memory cell. The resistive memory is integrated on the drain-side of the transistor. Different voltage biases are applied to each terminal during forming, SET and RESET operations.

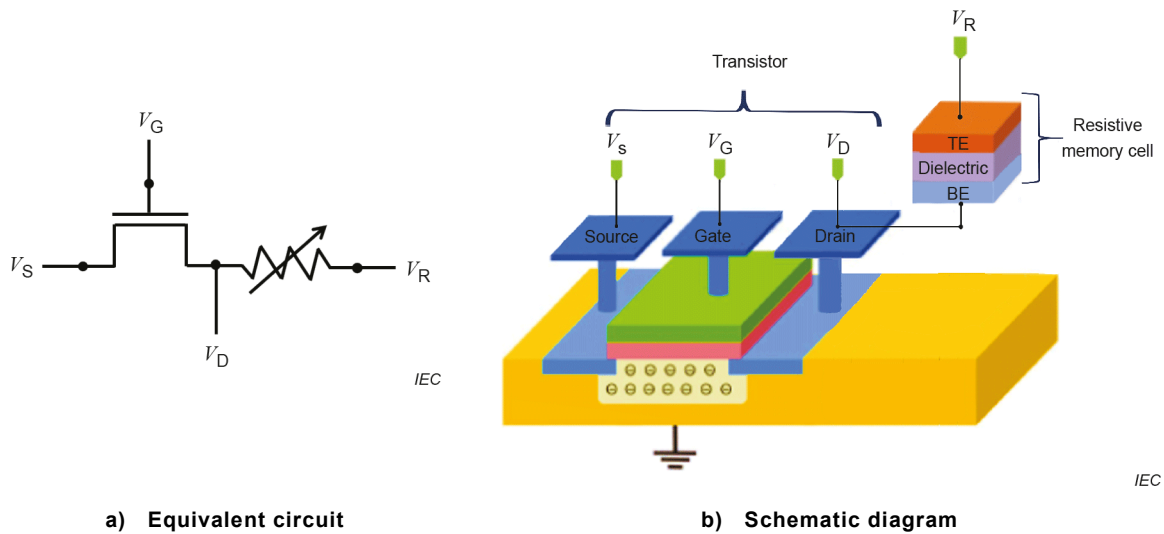


Figure 1 – 1T1R resistive memory cell

Resistive memory is composed of an insulating oxide material sandwiched between two metal electrodes. The bottom electrode (BE) of the cell is connected to the drain of transistor. The V_R is applied on the top electrode of the 1T1R resistive memory cell with V_S grounded. The transistor limits the current during the forming and SET operations by the gate voltage, V_G .

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5 Test method

5.1 General

IEC 62951-9:2022

Test procedures for 1T1R resistive memory cells are performed as shown in Figure 2. First, 1T1R resistive memory cell (DUT) is mounted on a test fixture, and its electrical characteristics are measured by varying voltage, current and temperature. For measuring and characterizing these devices accurately, ultra-high accuracy sensors shall be employed.

5.2 Test equipment and tools

5.2.1 General

A variety of experimental approaches have been employed to test 1T1R resistive memory cells. Semiconductor parameter analyzer is a test instrument that integrates multiple measurement and analysis capabilities to perform the current-voltage (I-V) and capacitance measurements (C-V (capacitance-voltage), C-f (capacitance-frequency), and C-t (capacitance-time)) of 1T1R resistive memory cells. The semiconductor parametric test is a fundamental measurement to determine the characteristics of a semiconductor device and its manufacturing process.

The key measurement component of the parameter analyzer is a source measure unit (SMU). The SMU is a measurement module that combines the capabilities of a voltage/current source and a voltage/current meter into a single module. Because the source and measurement circuitry are closely integrated, one can achieve far better accuracy and higher resolution with less measurement error than using various independent instruments to make the same measurement. To perform ultra-fast (transient) I-V measurements, the pulse generator unit (PGU) provides ultra-fast voltage waveform generation and signal observation on different channels of integrated sourcing and measurement. Hot chuck is also an important tool to be used together with a probe for evaluating temperature characteristics of 1T1R resistive memory cells.

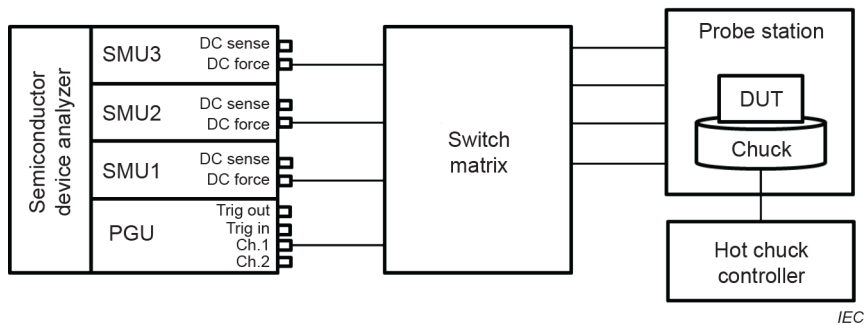


Figure 2 – Block diagram of the measurement setup of 1T1R resistive memory cells

5.2.2 Read

Figure 3 a) corresponds to the circuit diagram and Figure 3 b) corresponds to the voltage-time graph to exhibit the read operation of 1T1R resistive memory cell. The current value, I_{Read} , is measured to calculate the resistance of resistive memory, R_R , when V_{Read} with pulse width t_{Read} is applied across the resistive memory.

Figure 4 shows the exemplary cumulative probability distribution of HRS and LRS of 1T1R resistive memory cells with intermediate resistance trip point resistance, R_{TRP} . To be considered as an application for the field case, R_{HRS}/R_{LRS} in Figure 4 should be equal to or greater than 2.

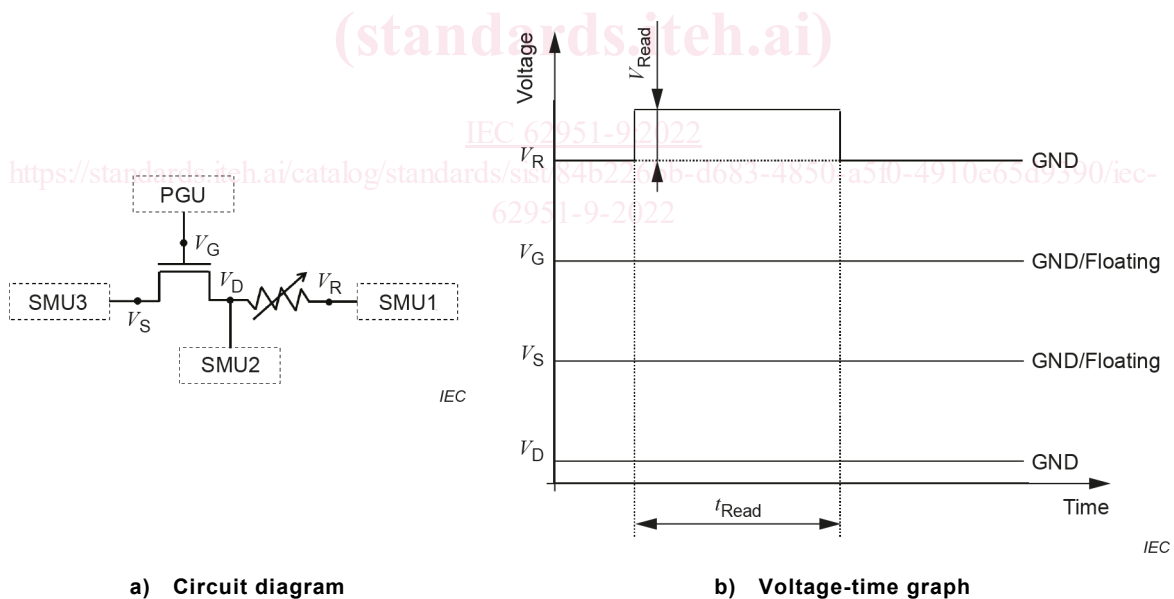


Figure 3 – Read operation of 1T1R resistive memory cell